



Beam Initiative

The Fine Line: Summer 2017 Videos for the eBeam Community

Shot Talk: A Word from Our Sponsor

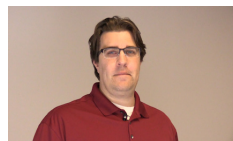
Aki Fujimura, CEO of D2S, highlights the company's latest developments as it celebrates its 10th anniversary, as well as recaps hot topics at Photomask Japan such as deep learning, pixel-level dose correction, and the state of EUV, multi-beam and nanoimprint lithography (NIL).



A Japanese version of the video can be found [here](#). Leo Pang, chief product officer of D2S, also recaps these developments in [Chinese](#).

Tech Talk

In Part 2 of a mask modeling series, Ryan Pearman of D2S reviews the challenges of mask modeling in the EUV era, including the need for dose/shape separation and mid-range correction, and the impact of GPU acceleration. Part 1 on mask modeling in the multi-beam era, which was recorded at the eBeam Initiative event at this past SPIE Advanced Lithography, can be viewed [here](#).



Perspectives

Jim Wiley, president of SPIE BACUS, talks about this year's merger of the EUV Lithography Symposium and the SPIE Photomask Conference—including what's new and different, the latest updates on the event location, and topics to look forward to such as EUV mask inspection—as well as his predictions on machine learning.



Video Archive

The Fine Line: Spring 2017 Edition



Shot Talk:
[Aki Fujimura, D2S](#)



Shot Talk:
[Leo Pang, D2S](#)



Tech Talk:
[Tom Cecil, Synopsys](#)



Perspectives:
[Greg McIntyre](#)

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The eBeam Initiative provides a forum for educational and promotional activities regarding new semiconductor manufacturing approaches based on electron beam (eBeam) technologies. Its goals are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in eBeam technologies throughout the semiconductor ecosystem. For more information, please email requests@ebeam.org or visit www.ebeam.org